

EAST Search History

| Ref # | Hits | Search Query | DBs | Default Operator | Plurals | Time Stamp |
|-------|-------|---|---|------------------|---------|---------------------|
| L2 | 12064 | "Hewlett-Packard Development ".asn. | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/23 07:32 |
| L3 | 53 | "6165911" | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/23 07:32 |
| L4 | 17 | 2 and L3 | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/23 07:32 |
| L5 | 456 | nano?imprint lithography | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/23 07:33 |
| L6 | 17 | L5 and (silicon near substrate) and (imprint pattern) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/23 07:33 |
| L7 | 0 | 2 and L6 | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/23 07:33 |
| L8 | 15 | 2 and 5 | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/23 07:33 |
| L9 | 5 | L2 and (silicon near substrate) and (imprint pattern) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/23 07:34 |

| | | | | | | |
|----|----|---|---|-----|-----|---------------------|
| S1 | 2 | ("5948470").PN. or ((2002/042027) or (2002/005391)).CCLS. | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2008/05/19 12:45 |
| S2 | 0 | (2002/042027).CCLS. | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2008/05/19 13:35 |
| S3 | 0 | 2002/042027 | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/19 13:35 |
| S4 | 0 | 2002/042027 | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/19 13:36 |
| S5 | 0 | (stephen chou).inv. | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/19 13:36 |
| S6 | 4 | ("2002042027").PN. | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2008/05/19 13:37 |
| S7 | 89 | (stephen near chou).inv. | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/19 13:43 |
| S8 | 0 | S7 and @pd="02200411" | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/19 13:44 |
| S9 | 0 | (2002/0005391).CCLS. | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2008/05/19 13:46 |

| | | | | | | |
|-----|----|-----------------------|---|-----|-----|---------------------|
| S10 | 0 | (2002/005391).CCLS. | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2008/05/19 13:46 |
| S11 | 0 | 2002/005391 | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/19 13:46 |
| S12 | 0 | 2002/0005391 | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/19 13:47 |
| S13 | 0 | thurn-albrecht.inv. | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/19 13:47 |
| S14 | 10 | (thurn-albrecht).inv. | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/19 13:48 |
| S15 | 75 | "5948470" | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/19 13:50 |
| S16 | 2 | ("5948470").PN. | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2008/05/19 13:50 |
| S17 | 0 | (wo01/33300).CCLS. | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2008/05/19 13:50 |
| S18 | 20 | 01/33300 | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/19 13:51 |

| | | | | | | |
|-----|--------|---|---|-----|-----|---------------------|
| S19 | 0 | ("wo20010500").PN. | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2008/05/19 13:52 |
| S20 | 117005 | "20010500" | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/19 13:53 |
| S21 | 0 | wo?20010500 | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/19 13:53 |
| S22 | 0 | wo20010500 | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/19 13:53 |
| S23 | 2 | ("7082876").PN. | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2008/05/19 13:54 |
| S24 | 0 | WO "20010500" | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/19 14:26 |
| S25 | 0 | method of reducing pattern distortions during imprint lithography | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/19 14:30 |
| S26 | 15 | reducing pattern distortions during imprint lithography | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/19 14:31 |
| S27 | 1 | wo-0133300-\$.did. | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/19 14:32 |

| | | | | | | |
|-----|----------|---|---|-----|----|---------------------|
| S28 | 2 | de-10030016-\$.did. | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/19 14:34 |
| S29 | 32985954 | @pd<"20031112" | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/20 10:04 |
| S30 | 1308003 | template or mold | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/20 10:05 |
| S31 | 7481 | S30 near substrate | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/20 10:06 |
| S32 | 289533 | silicon near3 substrate | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/20 10:06 |
| S33 | 436 | S31 with (polymer or pmma or pmgi or photoresist) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/20 10:07 |
| S34 | 168 | S29 and S30 and S33 | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/20 10:07 |
| S35 | 798153 | nanometer or nm or nanoprint or nanopattern | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/20 10:09 |
| S36 | 48 | S34 and S35 | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/20 10:09 |

| | | | | | | |
|-----|----------|---|---|-----|----|---------------------|
| S37 | 28 | S29 and S33 and S32 and S35 | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/20 10:14 |
| S38 | 3465 | (ge or germanium) near semiconductor | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/20 13:06 |
| S39 | 126033 | semiconductor adj layer | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/20 13:06 |
| S40 | 207948 | silicon near substrate | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/20 13:07 |
| S41 | 798313 | nm or nanometer or nanoprint or nanoimprint or nanopattern | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/20 13:08 |
| S42 | 32985954 | @pd<"20031112" | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/20 13:09 |
| S43 | 3465 | (ge or germanium) near semiconductor | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/20 13:11 |
| S44 | 126033 | semiconductor adj layer | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/20 13:11 |
| S45 | 798313 | nm or nanometer or nanoprint or nanoimprint or nanopattern | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/20 13:11 |

| | | | | | | |
|-----|----------|--|---|-----|----|---------------------|
| S46 | 0 | S43 and S44 and s "40" and S45 | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/20 13:11 |
| S47 | 207948 | silicon near substrate | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/20 13:11 |
| S48 | 322 | S43 and S44 and S47 and S45 | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/20 13:11 |
| S49 | 32985954 | @pd< "20031112" | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/20 13:12 |
| S50 | 93 | S48 and S49 | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/20 13:12 |
| S51 | 28 | S50 and (pmma or polymer or photoresist or pmgi) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/20 13:13 |
| S52 | 226110 | template | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/20 14:32 |
| S53 | 55209 | S52 and "43" and "45" and "51" | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/20 14:33 |
| S54 | 3465 | (ge or germanium) near semiconductor | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/20 14:34 |

| | | | | | | |
|-----|----------|---|---|-----|----|---------------------|
| S55 | 126033 | semiconductor adj layer | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/20 14:34 |
| S56 | 798313 | nm or nanometer or nanoprint or nanoimprint or nanopattern | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/20 14:34 |
| S57 | 207948 | silicon near substrate | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/20 14:34 |
| S58 | 322 | S54 and S55 and S57 and S56 | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/20 14:34 |
| S59 | 32985954 | @pd<"20031112" | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/20 14:34 |
| S60 | 93 | S58 and S59 | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/20 14:34 |
| S61 | 28 | S60 and (pmma or polymer or photoresist or pmgi) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/20 14:34 |
| S62 | 0 | S52 and S54 and S56 and S61 | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/20 14:34 |
| S63 | 463 | (silicon near substrate) and (polymer or pmma or pmgi or photoresist) and (semiconductor near (ge or germanium)) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/20 14:36 |

| | | | | | | |
|-----|---------|---|---|-----|----|---------------------|
| S64 | 159 | S63 and S59 | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/20 14:37 |
| S65 | 13 | S60 and (pmma or polymer or pmgi) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/20 14:47 |
| S66 | 346 | S59 and S56 and S52 and S57 and germanium | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/05/20 14:48 |
| S67 | 4630 | ((nano?imprint\$3) or (nano imprint \$3) or (imprint adj lithograp\$6)) or nanolithograp\$5 or (nano?lithogra \$6)) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/21 10:34 |
| S68 | 1602236 | germanium or ge | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/21 10:35 |
| S69 | 268466 | (pmma or polymethylmeth\$ or pmgi or polymethylgluta\$ or az5214e or photoresist) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/21 10:38 |
| S70 | 1112 | S67 and S68 | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/21 10:38 |
| S71 | 101 | S67 same S68 | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/21 10:38 |
| S72 | 1540 | S67 and S69 | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/21 10:41 |

| | | | | | | |
|-----|-------|--|---|-----|----|---------------------|
| S73 | 480 | S67 same S69 | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/21 10:42 |
| S74 | 26586 | S68 and S69 | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/21 10:42 |
| S75 | 3507 | S68 same S69 | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/21 10:42 |
| S76 | 10 | S71 and S73 and S75 | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/21 10:42 |
| S77 | 65 | shunpu.inv. | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/21 11:21 |
| S78 | 19543 | template.ti. | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/21 11:21 |
| S79 | 4 | S78 and S77 | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/21 11:21 |
| S80 | 3 | ("4407695" "4512848" "4801476").PN. | US-PGPUB; USPAT; USOCR | ADJ | ON | 2008/07/21 12:38 |
| S81 | 34806 | germanium with (aluminum or al or indium or gold) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/21 14:15 |
| S82 | 5375 | (germanium with (aluminum or al or indium or gold)) with semiconductor | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/21 14:16 |

| | | | | | | |
|-----|----------|--|---|-----|-----|---------------------|
| S83 | 30322507 | @ad<"20050513" | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/21 14:20 |
| S84 | 3671 | S82 and S83 | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/21 14:20 |
| S85 | 92 | S84 and substrate and pmma | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/21 14:20 |
| S86 | 505 | ((germanium with (aluminum or al or indium or gold)) with semiconductor) with substrate) and S69 | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/21 14:31 |
| S87 | 938302 | "427".clas. or "428".clas. or "430". clas. or "425".clas. or "264".clas. or "156".clas. | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/21 14:35 |
| S88 | 572282 | S83 and S87 | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/21 14:36 |
| S89 | 2 | ("4512848").PN. | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | OR | OFF | 2008/07/21 14:41 |
| S90 | 483 | photoresist and template and silicon and germanium and S69 and pattern and (nanometer or angstrom or nm) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/21 15:03 |
| S91 | 108 | S90 and S88 | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/21 15:04 |

| | | | | | | |
|------|----------|--|---|-----|----|---------------------|
| S92 | 108 | S91 and germanium | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/21 15:13 |
| S93 | 268466 | (pmma or polymethylmeth\$ or pmgi or polymethylgluta\$ or az5214e or photoresist) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/21 17:12 |
| S94 | 30322507 | @ad<"20050513" | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/21 17:12 |
| S95 | 938302 | "427".clas. or "428".clas. or "430". clas. or "425".clas. or "264".clas. or "156".clas. | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/21 17:12 |
| S96 | 572282 | S94 and S95 | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/21 17:12 |
| S97 | 483 | photoresist and template and silicon and germanium and S93 and pattern and (nanometer or angstrom or nm) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/21 17:12 |
| S98 | 108 | S97 and S96 | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/21 17:12 |
| S99 | 108 | S98 and germanium | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/21 17:12 |
| S100 | 34 | S99 and (imprint with lithography) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/21 17:12 |

| | | | | | | |
|------|----|--|---|-----|----|---------------------|
| S101 | 34 | (US-20060076717-\$ or US-20060062867-\$ or US-20060035164-\$ or US-20040141168-\$ or US-20040124566-\$ or US-20040086793-\$ or US-20040053146-\$ or US-20040022888-\$ or US-20040021254-\$ or US-20040007799-\$ or US-20030205658-\$ or US-20030205657-\$ or US-20020115002-\$ or US-20020098426-\$ or US-20020094496-\$ or US-20020093122-\$).did. or (US-7374968-\$ or US-7338275-\$ or US-7229273-\$ or US-7179079-\$ or US-7140861-\$ or US-7132225-\$ or US-7077992-\$ or US-7070405-\$ or US-7037639-\$ or US-7027156-\$ or US-6954275-\$ or US-6932934-\$ or US-6926921-\$ or US-6921615-\$ or US-6919152-\$ or US-6916585-\$ or US-6916584-\$ or US-6696220-\$).did. | US-PGPUB; USPAT | ADJ | ON | 2008/07/21 17:28 |
| S102 | 34 | S101 and germanium | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/21 17:29 |
| S103 | 1 | S102 not (silicon adj germanium) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/21 17:31 |
| S104 | 1 | S103 and germanium and S93 and S97 | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/21 17:35 |
| S105 | 13 | ("20030213382" "20040163758" "5512131" "6060121" "6365059" "6407443" "6518194" "6547940" "6599824" "6709929" "6755984" "6764833" "7060625").PN. | US-PGPUB; USPAT; USOCR | ADJ | ON | 2008/07/22 07:59 |
| S106 | 5 | "6506660" | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/22 08:08 |

| | | | | | | |
|------|------|--|---|-----|----|---------------------|
| S107 | 34 | (US-20060076717-\$ or US-20060062867-\$ or US-20060035164-\$ or US-20040141168-\$ or US-20040124566-\$ or US-20040086793-\$ or US-20040053146-\$ or US-20040022888-\$ or US-20040021254-\$ or US-20040007799-\$ or US-20030205658-\$ or US-20030205657-\$ or US-20020115002-\$ or US-20020098426-\$ or US-20020094496-\$ or US-20020093122-\$).did. or (US-7374968-\$ or US-7338275-\$ or US-7229273-\$ or US-7179079-\$ or US-7140861-\$ or US-7132225-\$ or US-7077992-\$ or US-7070405-\$ or US-7037639-\$ or US-7027156-\$ or US-6954275-\$ or US-6932934-\$ or US-6926921-\$ or US-6921615-\$ or US-6919152-\$ or US-6916585-\$ or US-6916584-\$ or US-6696220-\$).did. | US-PGPUB; USPAT | ADJ | ON | 2008/07/22 09:59 |
| S108 | 34 | S107 and germanium | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/22 09:59 |
| S109 | 1666 | germanium with sputter\$4 | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/22 10:17 |
| S110 | 26 | S109 and silicon and pmma | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/22 10:17 |
| S111 | 34 | S107 and nm | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/22 12:33 |
| S112 | 16 | S107 and (layer with nm) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/22 12:34 |

| | | | | | | |
|------|----|---|---|-----|----|---------------------|
| S113 | 7 | S107 and ((thick or thickness) with nm) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/22 12:37 |
| S114 | 0 | S107 and ((thick or thickness) with (mask or polymer)) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/22 12:39 |
| S115 | 0 | S107 and ((thick or thickness) with (resist)) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/22 12:39 |
| S116 | 4 | S107 and ((thick or thickness) with (\$resist)) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/22 12:40 |
| S117 | 3 | S107 and pmma | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/22 13:03 |
| S118 | 1 | S107 and polymethylmethacrylate | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/22 13:04 |
| S119 | 25 | (US-20020042027-\$ or US-20020005391-\$ or US-20030205658-\$ or US-20030205657-\$ or US-20050281982-\$ or US-20050221218-\$ or US-20040141168-\$ or US-20040124566-\$ or US-20040086793-\$ or US-20040053146-\$ or US-20040053009-\$ or US-20020168592-\$ or US-20020115002-\$ or US-20020094496-\$ or US-20060035164-\$ or US-20040170925-\$).did. or (US-5948470-\$ or US-6753130-\$ or US-4512848-\$ or US-7374968-\$ or US-7060625-\$ or US-6755984-\$ or US-6365059-\$ or US-5512131-\$).did. or (US-5948470-\$ or WO-0133300-A-\$ or DE-10030016-A-\$).did. | US-PGPUB; USPAT; DERWENT | ADJ | ON | 2008/07/22 13:07 |

| | | | | | | |
|------|--------|---|---|-----|----|---------------------|
| S120 | 10 | S119 and pmma | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/22 13:08 |
| S121 | 23 | S119 and nm | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/22 13:15 |
| S122 | 1 | ("20030071016").PN. | US-PGPUB; USPAT; USOCR | ADJ | ON | 2008/07/22 16:23 |
| S123 | 199 | (lee near heon).inv. | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/22 16:42 |
| S124 | 15 | S123 and silicon and substrate and pattern and imprint | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/22 16:43 |
| S125 | 177981 | "430".clas. or "216".clas. | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/22 16:47 |
| S126 | 533 | S125 and silicon and substrate and pattern and imprint | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/22 16:47 |
| S127 | 190 | S126 and template | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/22 16:48 |
| S128 | 32 | S127 and imprint pattern | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/22 16:49 |
| S129 | 5 | 2003/0071016 | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/22 16:52 |

| | | | | | | |
|------|-----|--|---|-----|----|---------------------|
| S130 | 2 | "20030071016" | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/22 16:52 |
| S131 | 456 | nano?imprint lithography | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/22 17:00 |
| S132 | 17 | S131 and (silicon near substrate) and (imprint pattern) | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/22 17:01 |
| S133 | 53 | "6165911" | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/22 17:05 |
| S134 | 4 | "6673714" | US-PGPUB; USPAT; USOCR; FPRS; EPO; JPO; DERWENT; IBM_TDB | ADJ | ON | 2008/07/22 17:07 |

7/23/2008 8:29:34 AM

C:\Documents and Settings\dbrown\My Documents\EAST\Workspaces\10534931.wsp